ME597/PHYS57000 Fall Semester 2010 Lecture 01 Quantum Tunneling The STM – basic idea

Ron Reifenberger Birck Nanotechnology Center Purdue University

Suggested Reading:

• G. Binnig, H. Rohrer, Ch. Gerber, E. Weibel, "Tunneling through a controllable vacuum gap", Appl. Phys. Lett. **40**, 178 (1982).

• G. Binnig, H. Rohrer, Ch. Gerber, E. Weibel, Surface studies by scanning tunneling microscopy" Phys. Rev. Lett. **49**, 57 (1982).

• P.K. Hansma and J. Tersoff, "Scanning tunneling microscopy", J. Appl. Phys. **61**, R1 (1987).

Critical Realization (circa 1980)

Require a proximal probe (a sharp tip) to locally interrogate the surface of a bulk material

A Fundamental Breakthrough

Dual Character

• **Describes the wave field of a particle; the so-called matter wave**

Physics of Field Emission (~1925)

The electron wavefunctions for a square barrier can be analytically solved

 $\frac{2}{2}$ $\frac{2m}{2}$

 $\alpha^2 = \frac{2m(V_o -)}{r^2}$

2

 $2m(V_o - E)$

 \hbar

2

 $k^2 = \frac{2mE}{l^2}$

2

 \hbar

11

2

 \hbar

2

 $k^2 = \frac{2mE}{l^2}$

Calculating the Transmission Probability

The classical expression for current density produced by a charge q with velocity v is given by

j=qv

Now, if a single electron is described by a wavefunction Ψ(z,t), then the equivalent QM expression for the current is

$$
j=-|e|
$$

where $\langle v \rangle = \frac{d}{dt}\int_{-\infty}^{\infty} \psi^*(z,t) z \psi(z,t) dz$

Evaluating this expression using the time-dependent Schroedinger equation, we can define a probability current density given by

$$
j = \frac{-i\hbar}{2m} \left[\psi^* \frac{d\psi}{dz} - \psi \frac{d\psi^*}{dz} \right]
$$

Transmitted current: * * $\frac{d\psi_3}{d\psi_4}$ $\frac{d\psi_3}{d\psi_5}$ $\frac{d\psi_1}{d\psi_1}$ $j_{\textit{trans}} = \frac{-i\hbar}{2m} \left| \psi^*_3 \frac{d\psi_3}{dz} - \psi_3 \frac{d\psi^*_3}{dz} \right| = \frac{\hbar k}{m} |D|$ $=\frac{u\mu}{2m}\left[\psi_3^*\frac{u\psi_3}{dz}-\psi_3\frac{u\psi_3}{dz}\right]=$ $\hbar\big[\mathbb{I}_{\mathscr{M}^*}d\psi_3\big] = \hbar\big[\mathscr{U}^*\big] = \hbar\big[$

Incident current: * * $\frac{u\psi_1}{\psi_1}$ $\frac{u\psi_1}{\psi_1}$ $j_{inc} = \frac{-i\hbar}{2m} \left| \psi_1^* \frac{d\psi_1}{dz} - \psi_1 \frac{d\psi_1^*}{dz} \right| = \frac{\hbar k}{m}$ $=\frac{u^2}{2m}\left[\psi_1^*\frac{u\psi_1}{dz}-\psi_1\frac{u\psi_1}{dz}\right]=$ $\hbar\big|_{\mathcal{M}^*} d\psi_1 = d\psi_1^*\big|_{\mathcal{M}^*} d\psi_1^*\big|_{\mathcal{M}^*}$

Transmission Probability:

$$
T = \frac{j_{trans}}{j_{inc}} = |D|^2 = \frac{1}{1 + \frac{(k^2 + \alpha^2)^2}{4k^2 \alpha^2} \sinh^2(\alpha d)}
$$
 Valid for E-V_o

if $\alpha d \gg 1$ *(wide barrier, low energy)*

$$
T \approx \frac{16k^2\alpha^2}{(k^2 + \alpha^2)^2}e^{-2\alpha d} \qquad \alpha \sim 10 - 15 \, nm^{-1}
$$

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http://phet.colorado.edu/simulations/sims.php?sim=Quantum_ Tunneling_and_Wave_Packets

http://hyperphysics.phy-astr.gsu.edu/Hbase/quantum/barr.html#c1

Useful summary of barrier penetration

As a particle approaches the barrier, it is described by a free particle wavefunction. When it reaches the barrier, it must satisfy the Schrodinger equation in the form

$$
\frac{-\hbar^2}{2m}\frac{\partial^2\Psi(x)}{\partial x^2} = (E - U_0)\Psi(x)
$$

What to do??

Use insights gained from square barrier problem

very similar in form to T calculated earlier

To make current flow, apply bias voltage ∆**V**

Useful to define the Local Density of States (LDOS):

$$
\rho(z,E) \equiv \frac{1}{\varepsilon} \sum_{E-\varepsilon}^{E} \left| \psi_n(z) \right|^2
$$

ρ**(z,E) measures**

electrons/volume

energy interval

at a GIVEN distance z from substrate 18**and at a GIVEN energy E**

The LDOS has a few nice features:

- **It is independent of the volume of metal**
- **It is a number (for given z & E) that reflects the energy band structure of metal**
- **It can be used to obtain an expression for the current that flows**

Note that:
$$
\rho(0, E) = \frac{1}{\varepsilon} \sum_{E-\varepsilon}^{E} \left| \psi_n(0) \right|^2
$$

$$
= \frac{1}{e \Delta V} \sum_{E-e\Delta V}^{E} \left| \psi_n(0) \right|^2
$$

so

$$
I \propto probability \ of \ tunneling = \sum_{E_F - e\Delta V}^{E_F} |\psi_n(0)|^2 e^{-2\alpha_n d}
$$

$$
= e\Delta V \rho(0, E_F) e^{-2\alpha d} \quad \text{wh} \ \text{re} \ e\Delta V \to 0
$$

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LDOS Calculations

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Cluster-model density functional study of a $W-Cu(1\ 0\ 0)$ STM junction

L. Lamare^{a,*}, H. Aourag^b, J.-P. Dufour^a

^aLaboratoire de Physique de l'Université de Bourgogne, ESA 5027, 9 rue Alain Savary, BP 400, F-21011, Dijon, France ^bLaboratoire de Sciences des Matériaux, Université Djillali Lyabes, Sidi Bel Abbes, 22000, Algeria

Fig. 1. Geometries of the W-Cu interacting clusters: (a) W_{14} -Cu₁₃; (b) W_{14} -Cu₂₅.

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Total:

Fig. 5. Contour maps of the total and symmetry-projected electronic valence density of W_{14} –Cu₁₃ cluster for a tip–sample separation of 4 Å: (a) total density (including core states); (b) A1-density; (c) B1-density; (d) E-density. Black diamonds indicate the atomic positions.

W electron configuration: 1s2, 2s2, 2p6, 3s2, 3p6, 3d10, 4f14, 5s2, 5p6, 5d4, 6s2

Typical values

$$
\alpha(in m^{-1}) = \sqrt{\frac{2m(V_o - E)}{\hbar^2}}
$$

\n
$$
\alpha(in nm^{-1}) = 5.1\sqrt{\varphi(in eV)} \quad \text{[convenient units]}
$$

\n
$$
I(z) = I(0)e^{-2\alpha z}
$$

\n
$$
I(z+0.1n m) = I(0)e^{-2\alpha(z+0.1)} = I(z)e^{-2\alpha(0.1)}
$$

\nfor $\varphi = 5.09 eV \Rightarrow \alpha = 11.51 nm^{-1}$, then
\n
$$
I(z+0.1n m) = 0.1I(z)
$$

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Table from C. Julian Chen, Introduction to Scanning Tunneling Microscopy, 2nd Edition **(Oxford University Press, Oxford) 2008.**

How to achieve a controllable small vacuum gap?

What's d?

Binnig and Rohrer, 1981

Using tip geometry, d might be well defined!

Does $I(z) \sim e^{-2ad}$??

Tunneling through a controllable vacuum gap

G. Binnig, H. Rohrer, Ch. Gerber, and E. Weibel IBM Zurich Research Laboratory, 8803 Rüschlikon-ZH, Switzerland

(Received 30 September 1981; accepted for publication 4 November 1981)

We report on the first successful tunneling experiment with an externally and reproducibly adjustable vacuum gap. The observation of vacuum tunneling is established by the exponential dependence of the tunneling resistance on the width of the gap. The experimental setup allows for simultaneous investigation and treatment of the tunnel electrode surfaces.

PACS numbers: 73.40.Gk

FIG. 2. Tunnel resistance and current vs displacement of Pt plate for different surface conditions as described in the text. The displacement origin is arbitrary for each curve (except for curves B and C with the same origin). The sweep rate was approximately 1 Å/s. Work functions $\phi = 0.6$ eV and 0.7 eV are derived from curves A, B, and C, respectively. The instability which occurred while scanning B and resulted in a jump from point I to II is attributed to the release of thermal stress in the unit. After this, the tunnel unit remained stable within 0.2 Å as shown by curve C. After repeated cleaning and in slightly better vacuum, the steepness of curves D and E resulted in $\phi = 3.2$ eV. 25

 $I(x,y) = e\Delta V\rho(z=0.6 \text{ nm}, x, y; E_F)$ The Scanning Tunneling Microscope

adjusting tip height.

If tip scanned in controllable way \rightarrow a microscope! 27

A z-height microscope!

Figure 2.18. Constant-height (top sketch) and constant-current (bottom sketch) imaging mod of a scanning tunneling microscope. (From T. Bayburt, J. Carlson, B. Godfrey, M. Shand Retzlaff, and S. G. Sligar, in Handbook of Nanostructured Materials and Nanotechnology H. S. Nalwa, ed., Academic Press, Boston, 2000, Vol. 5, Chapter 12, p. 641.)